	Application No.	Applicant(s))m
Notice of Allowability	09/963,482	LEE ET AL.	
	Examiner	Art Unit	7
	Michael D Masinick	2125	
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS	ars on the cover sheet wit (OR REMAINS) CLOSED in	h the correspondence address this application. If not included	
herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	GHTS. This application is s		
1. This communication is responsive to <u>May 21, 2004</u> .			:
2. \boxtimes The allowed claim(s) is/are <u>1,3-9 and 21-23</u> .			
3. \boxtimes The drawings filed on <u>27 September 2001</u> are accepted by	the Examiner.	•	•
 Acknowledgment is made of a claim for foreign priority un a)	der 35 U.S.C. § 119(a)-(d) c	or (f).	
1. Certified copies of the priority documents have	been received.		
2. Certified copies of the priority documents have	been received in Application	n No	
3. Copies of the certified copies of the priority doc	cuments have been received	in this national stage application	n from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		a reply complying with the requir	ements
 A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give 			ICE OF
6. CORRECTED DRAWINGS (as "replacement sheets") mus			
(a) ☐ including changes required by the Notice of Draftspers	· · · · · · · · · · · · · · · · · · ·	(PTO-948) attached	
 1) ☐ hereto or 2) ☐ to Paper No./Mail Date 			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment or	in the Office action of	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on th	e drawings in the front (not the ba	ck) of
DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT I	sit of BIOLOGICAL MATE	RIAL must be submitted. Not	e the
Attachment(c)			:
Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5. Notice of Inf	ormal Patent Application (PTO-1	52)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🗌 Interview Su	ımmary (PTO-413),	*
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0		Mail Date Amendment/Comment	
Paper No./Mail Date4. Examiner's Comment Regarding Requirement for Deposit	8. 🛛 Examiner's	Statement of Reasons for Allowa	ince
of Biological Material	9. Other		:
			8

Art Unit: 2125

DETAILED ACTION

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Kenneth Springer on July 8th, 2004.

Replace claim 1 with:

1. A method of performing a chemical vapor deposition processing comprising:

cleaning a process chamber at a first chamber pressure by producing a cleaning gas into the process chamber through a cleaning gas supply line;

pre-coating a film on inner sidewall of the process chamber at a chamber pressure lower than the first chamber pressure by introducing a deposition gas into the process chamber, wherein during said pre-coating, a backflow preventing gas is introduced into the process chamber through the cleaning gas supply line to prevent the deposition gas from flowing back toward the cleaning gas supply line;

loading a wafer into the process chamber after said the cleaning; and
depositing a film on the wafer at a chamber pressure lower than the first chamber
pressure by introducing a deposition gas into the process chamber, wherein during said
depositing, a backflow preventing gas is introduced into the process chamber through the
cleaning gas supply line to prevent the deposition gas from flowing back toward the

Claim 24 is cancelled.

cleaning gas supply line.

Application/Control Number: 09/963,482 Page 4

Art Unit: 2125

Allowable Subject Matter

2. Claims 1, 3-9, 21-23 are allowed.

3. The following is an examiner's statement of reasons for allowance:

4. While Taketa et al shows the use of a backflow prevention device using gas, neither this reference taken alone or in combination with the prior art of record disclose a backflow prevention system using backflow preventing gas introduced through the cleaning gas supply line to prevent the deposition gas from flowing back toward the cleaning gas supply line. It is this backflow prevention system as stated in the applicants arguments, in combination with the remaining elements and features of the invention, that the applicant's invention defines over the prior art of record.

5. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michael D Masinick whose telephone number is (703) 305-7738. The examiner can normally be reached on Mon-Fri, 7:30-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Leo Picard can be reached on (703) 308-0538. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Art Unit: 2125

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

L.P.P.

MDM

LEO PICARD
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2100